

In the Claims:

Please cancel claims 1, 3 and 8-12 without prejudice or disclaimer.

Please amend claim 6 as follows:

Claim 1 (currently canceled)

Claim 2 (previously canceled)

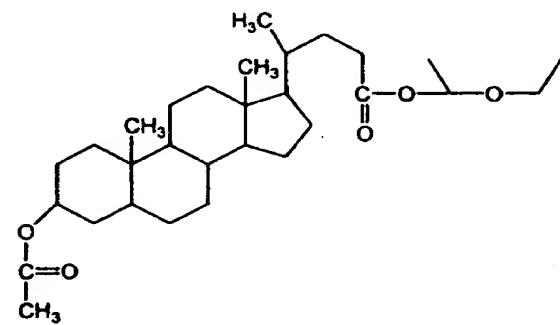
Claim 3 (currently canceled)

Claims 4-5 (previously canceled)

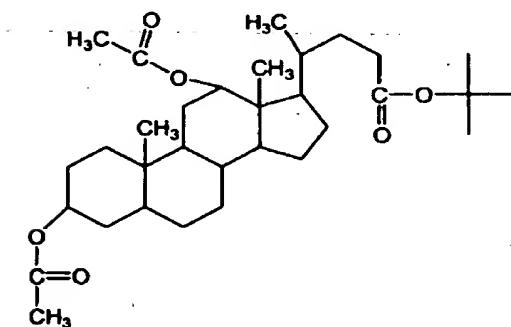
Claim 6 (currently amended) ~~The photoresist composition of claim 3 A photoresist composition comprising:~~

a photoresist polymer, a photoacid generator, an additive of following Formulas 3-7 and an organic solvent,

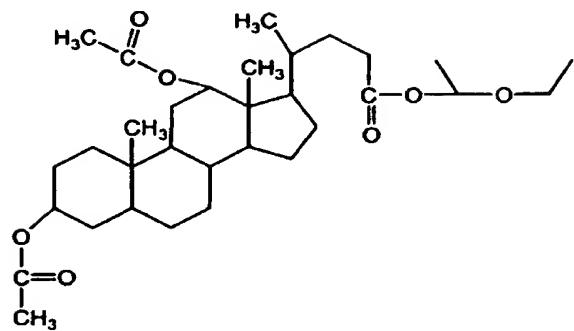
Formula 3



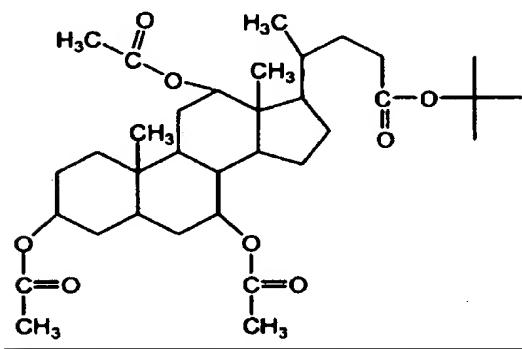
Formula 4



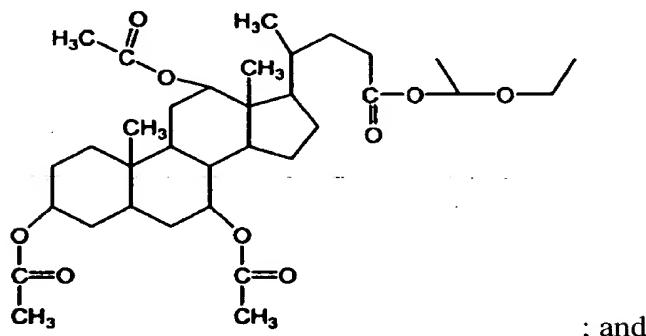
Formula 5



Formula 6



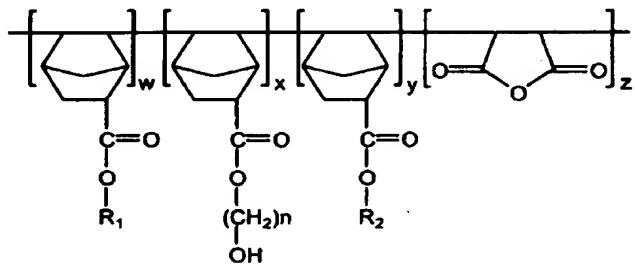
Formula 7



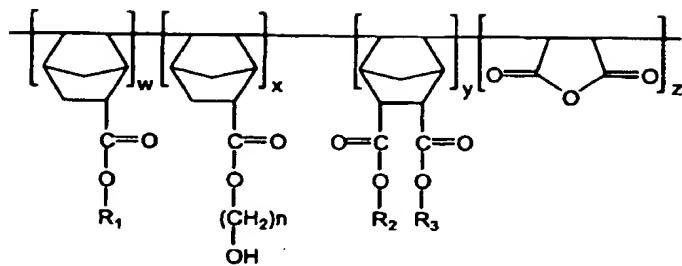
; and

wherein the photoresist polymer is a compound of following Formulas 8 or 9:

Formula 8



Formula 9



wherein, R<sub>1</sub> is an acid labile protecting group;

R<sub>2</sub> is hydrogen;

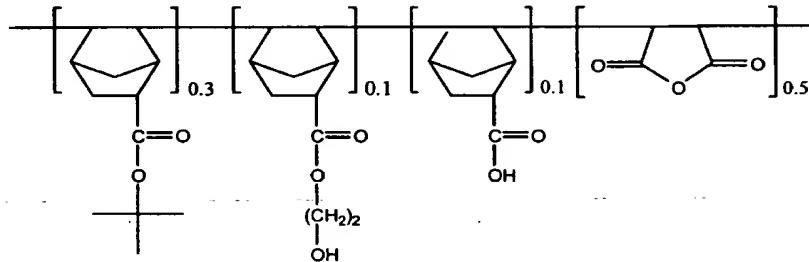
R<sub>3</sub> is hydrogen, selected from the group consisting of C<sub>1</sub>-C<sub>10</sub> alkyl, C<sub>1</sub>-C<sub>10</sub> alkoxyalkyl, and C<sub>1</sub>-C<sub>10</sub> alkyl containing at least one hydroxyl group (-OH);

n is an integer from 1 to 5; and

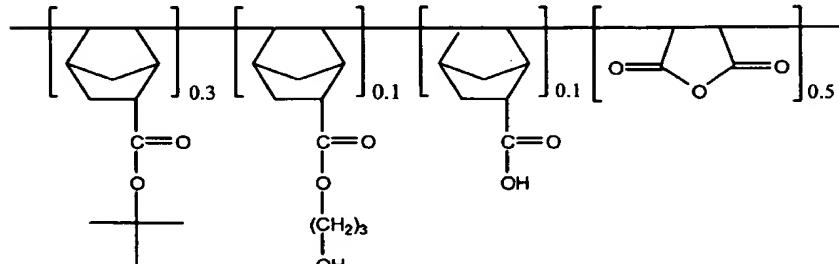
w, x, y and z individually denote the mole ratio of each monomer, preferably with proviso that w + x + y = 50mol%, and z is 50mol%.

Claim 7 (previously amended) The photoresist composition of claim 6 wherein the photoresist polymer is selected from the group consisting of compounds of following Formulas 10 to 13:

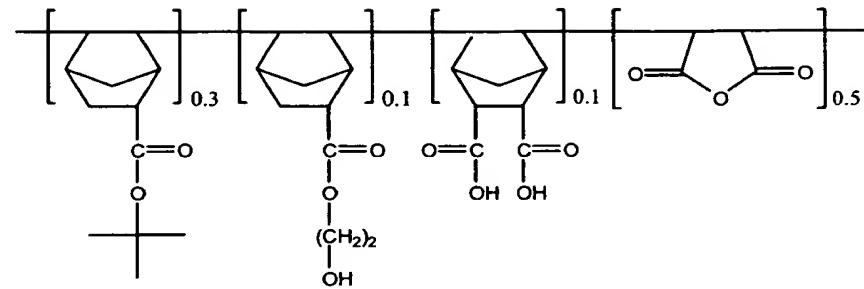
Formula 10



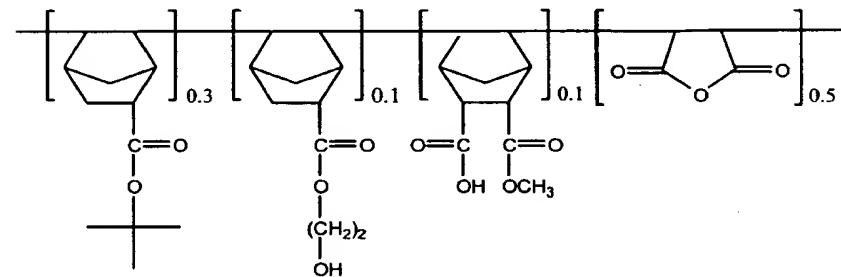
Formula 11



Formula 12



Formula 13



Claims 8-12 (currently canceled)

Claims 13-20 (previously canceled)